## FIS920030183US1

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Dureseti CHIDAMBARRAO, et al.

Group Art Unit: 2814

Appln. No.

: 10/605,108

Examiner: PHAM, Long

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For

: METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI

ON SI/GE SUBSTRATE

## COMMENTS UNDER 37 C.F.R. 1.312

Commissioner for Patents U.S. Patent and Trademark Office Customer Service Window, Mail Stop Randolph Building 401 Dulany Street Alexandria, VA 22314

Sir

In response to the Notice of Allowability, mailed by the Patent and Trademark Office on May 18, 2008, Applicant wishes to clarify the record with respect to the allowed claims. Applicant notes that claims 16-1822-28 and 30-39 are pending and should be indicated as being allowed.

Applicant also wishes to clarify that the claims in the present application recite a combination of features, and the basis for patentability of these claims is based upon the totality of the features recited therein.

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Should the Examiner have any questions or comments about the above, he is respectfully requested to contact the undersigned at the below-listed telephone number.

Respectfully submitted, Dureseti CHIDAMBARRAO, et al

Andrew M. Calderon Reg. No. 38,093

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